

Notice of References Cited	Application/Control No. 10/608,502	Applicant(s)/Patent Under Reexamination ENGELEN ET AL.	
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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	W	"Photoresist Stabilization System" Solid State Technology, vol. 27, no. 7, June 1984, pages 45-45, XP002067936 Washington, New York, USA see pages 45-46.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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